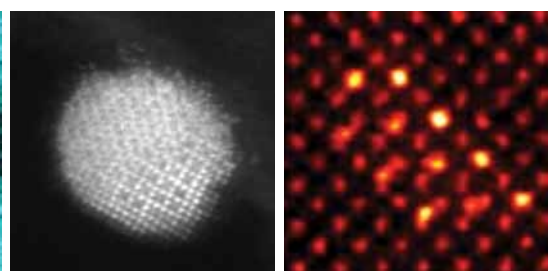
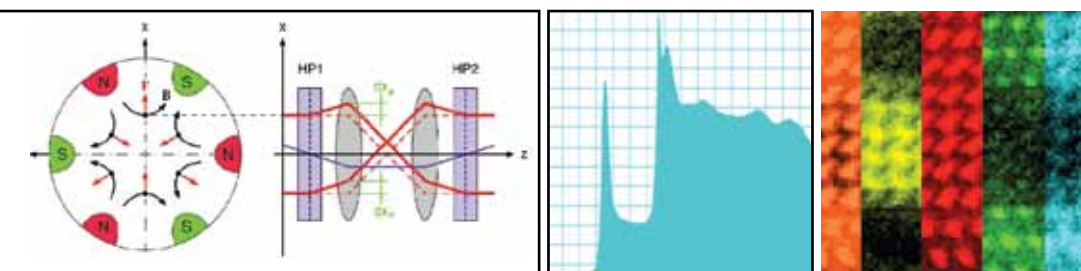


# CCEM Summer School on Electron Microscopy

**A 5-DAY COURSE** for users with experience in electron microscopy, on the fundamentals of aberration corrected imaging, electron energy loss spectroscopy, Lorentz microscopy, electron holography and the use of aberration-corrected electron microscopes. The aim is to provide students advice in solving characterization problems with the help of experts. The course will include lectures given by experts in the use of the technique and experts in electron optics, alignment and optimization of electron microscopes. Students will have plenty of opportunities for hands-on training on the alignment and operation of the electron microscopes with the experts from the microscope companies. Students are encouraged to bring their own TEM-ready samples. Two FEI Titan microscopes with correctors and monochromators and one FEI Osiris with SuperEDX will be used for training.



## June 11-15, 2012

**McMaster University**, Hamilton ON Canada. On-campus accommodation is available for confirmed registered students.

### COST

All meals and course notes are included in the registration fee ranging from **\$450.CDN**/full-time students to **\$1000.CDN**/industry researchers. Accommodation will be separate and the responsibility of attendees (*see full details on registration form*).

### REGISTRATION

**Register online** by **March 15** at the web address below. For inquiries, email: [ccem@mcmaster.ca](mailto:ccem@mcmaster.ca). Payment details are given on the registration form.

\*Places are limited to 15 registrants. Please contact us if you are interested to reserve a place.

### TOPICS

- Aberration-corrected TEM, STEM
- Alignment of microscopes with correctors
- Lorentz microscopy and holography
- Focal series reconstruction
- Images and diffraction simulations
- Monochromated EELS, EELS mapping
- New EDXS detectors
- Operation of monochromators

### LECTURERS

Various instructors from Academic Institutions and technical experts from manufacturers of microscopes and aberration correctors.

### CONFIRMED SPEAKERS:

H. Cheng (FEI); R. Egerton (U. Alberta); P. Hartel (CEOS); C. Kübel (KIT/Juelich Centrum); S. Lazar (FEI); G. Radtke (Marseille); P. Stadelmann (EPFL); E. Sourty (FEI); P. Tiemeijer (FEI); R. Twesten (Gatan); E. Voelkl (FEI); N. Zaluzec (ANL); J. Zweck (Regensburg)

<http://ccem.mcmaster.ca/outreach-courses>

